

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	) Confirmation No. 4499 ) ) Group Art Unit: 1765 ) Examiner: ALANKO A. K.
Inventor(s): Li Yao et al.	
Appln. No.: 10/689,043	
Filed: October 21, 2003	
For: Abrasive-Free chemical mechanical polishing composition and polishing process containing same	) ) )

## RESPONSE UNDER 37 C.F.R. §1.111

U.S. Patent and Trademark Office Randolph Building 401 Dulany Street Alexandria, Virginia 22314 MAIL STOP – AMENDMENT

Sir:

In response to the Office Action mailed on August 9, 2006 please consider the following amendments and remarks:

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.